

Final Announcement

Israeli BEAMeeting 2022



Time: Monday, May 16th, 2022, 9:00 am – 5:30 pm **Israel Daylight Time**
 Tuesday, May 17th, 2022, 9:00 am – 12:15 am **Israel Daylight Time**

Place: Benoziyo building - Weizmann Institute – Rehovot, ISRAEL (Drori Lecture Room)

BEAMeetings are a technical exchange platform for the direct write community focused on e-beam and laser lithography, data-preparation, PEC, process correction, and lithography simulation.

All partners, Israeli e-beam and laser lithography users are kindly invited. Please see below our final agenda.

If you would like to attend the meeting, please **register** with a short e-mail to:
marketing@genisys-gmbh.com and yair.arman@weizmann.ac.il with providing the following information:

Nr.	Please provide the following information when registering
1	Full Name
2	E-Mail
3	Company/Organisation
4	Will you attend day 1 or day 2 or 1+2?
	<i>If you come with a CAR, please also provide the following information (This is for entrance permit for cars in Weizmann and all the logistics):</i>
5	ID number/ passport number
6	If using ID, please Name in Hebrew, if using passport Name in English
7	Visitor mobile phone number or Email
8	Car license plate number, if rental please update when you have the number

The registration is free. If you have any colleagues who may be interested in the workshop, we would greatly appreciate your forwarding this information on to them.

We are looking forward to presenting you with an interesting and valuable workshop.

Final AGENDA

	Monday, May 16th	Start
All	Welcome to the BEAMeeting Introduction	09:00
Nezih Unal GenISys	GenISys Update	09:15
Thomas Michels GenISys	Product Update	09:45
Daniel Ritter GenISys	New GUI – BEAMER qt	10:15
Sven Bauerdick GenISys	ProSEM Update	10:30
	Coffee Break	11:00
Asi Solder Ben Gurion University	Fabry Perot Resonators Based on Grayscale Lithography for Hyperspectral Imaging	11:30
Aditya Reddy GenISys	3D PEC Differences	12:00
Kaivan Karami University of Glasgow	T-Gate fabrication process using multi-step development	12:30
	Lunch Break (served at Weizmann Institute San Martin building)	13:00
GenISys	TRACER – Process Calibration	14:15
Daniel Ritter GenISys	BEAMER – PEC Short Range, Optimal Contrast/Uniform Clearing	14:45
	Coffee Break	15:30
Zhengli Han Hebrew University	MEMS Controlled Plasmonic Colors for Sustainable Optical Displays	16:00
Emine Cagin NanoFrazor	Damage free nanostructuring on 2D materials using NanoFrazor technology	16:30
Nezih Unal GenISys	Wishes and Needs	17:00
	Closing	17:30

	Tuesday, May 17th	Start
All	Welcome	09:00
Daniel Ritter GenISys	BEAMER: Simulation and Metrology	09:15
Daniel Ritter GenISys	LAB: Process Transfer using Simulation (Bragg gratings from EBL to Projection)	09:45
Jonas Wiedenmann Multiphoton Optics	Introduction to Multiphoton Lithography and selected Application	10:15
	Coffee Break	10:45
HIMT	DWL66+ - the ultimate lithography research tool	11:15
Aditya Reddy GenISys	BEAMER for DWL	11:45
	Closing	12:15